10/750252

I hereby certify that this correspondence is being deposited with the United States Postal Service as first class mail in an envelope addressed to: Commissioner for Patents, P.O. Box 1450

Alexandria, VA 22312 on 14 Resumpy 2007.

REQUEST FOR CERTIFICATE OF CORRECTION UNDER 37 C.F.R. 1.322 Docket No. SUN-DA-136T Patent No. 7,101,759

Jeff Lloyd, Patent Attorney, Reg. No. 35,589

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant

Chang Hun Han

Issued

September 5, 2006

Patent No.

7,101,759 5

For

Methods for Fabricating Nonvolatile Memory Devices

Mail Stop Certificate of Corrections Branch Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

REQUEST FOR CERTIFICATE OF CORRECTION UNDER 37 CFR 1.322 (OFFICE MISTAKE)

Sir:

A Certificate of Correction (in duplicate) for the above-identified patent has been prepared and is attached hereto.

In the left-hand column below is the column and line number where errors occurred in the patent. In the right-hand column is the page and line number in the application where the correct information appears.

Patent Reads:	Amendment dated	April 10, 2006 Reads:
Column 3, line 27:	Claim 8:	
"fanning"	forming	Certificate
Column 4, line 2:	Claim 8:	FEB 2 2 2007
"tb-st"	first	of Correction

A true and correct copy of page 3 of the Amendment dated April 10, 2006, which supports Applicants' assertion of the errors on the part of the Patent Office, accompanies this Certificate of Correction.

Approval of the Certificate of Correction is respectfully requested.

Respectfully submitted,

leff Lloyd

Patent Attorney

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P.O. Box 142950

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JL/fes

Attachment: Page 3 of the Amendment dated April 10, 2006.

- 7. (Previously Presented) A method as defined in claim 1, wherein the polymer layers on the sidewalls of the sacrificial layer are separated by less than a lithographic minimum feature size.
 - 8. (Previously Presented) A method for fabricating a nonvolatile memory device comprising: forming an isolation layer and a non-active region in a semiconductor substrate; forming an oxide layer and a polysilicon layer on the substrate; forming a first sacrificial layer on the polysilicon layer; forming a second sacrificial layer on the first sacrificial layer;

etching the first sacrificial layer using the second sacrificial layer as a mask to form polymer layers on sidewalls of the first and the second sacrificial layers, the polymer layers being generated from the etching of the first sacrificial layer; and

forming a floating gate and a tunnel oxide using the first and the second sacrificial layers and the polymer layers as an etching mask.

- 9. (Previously Presented) A method as defined in claim 0, further comprising: removing the polymer layers, the first sacrificial layer and the second sacrificial layer; and forming an insulating layer and a polysilicon layer over the substrate, the floating gate, and the tunnel oxide.
- 10. (Previously Presented) A method as defined in claim 0, wherein the polymer layers on the sidewalls of the first and the second sacrificial layers are separated by less than a lithographic minimum feature size.
- 11. (Previously Presented) A method as defined in claim 0, wherein the second sacrificial layer comprises a patterned photoresistive material.

UNITED STATES PATENT AND TRADEMARK OFFICE

CERTIFICATE OF CORRECTION

PATENT NO.

7,101,759

Page 1 of 1

APPLICATION NO.:

10/750,252

DATED

September 5, 2006

INVENTOR

Chang Hun Han

It is certified that errors appear in the above-identified patent and that said Letters Patent is hereby corrected as shown below:

Column 3,

Line 27, "fanning" should read --forming--.

Column 4,

Line 2, "tb-st" should read --first--.

MAILING ADDRESS OF SENDER: Saliwanchik, Lloyd & Saliwanchik P.O. Box 142950 Gainesville, FL 32614-2950

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